

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Joseph Young J. PAIK

Serial No. 10/665,165

Filed: September 18, 2003



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: Group Art Unit:
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: Examiner:

For: FEEDBACK CONTROL OF A CHEMICAL MECHANICAL POLISHING PROCESS
FOR MULTI-LAYERED FILMS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of any cited U.S. Patents and U.S. Patent Publications are not being submitted in accordance with 37 CFR 1.98(a)(2)(i).

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

In accordance with 37 C.F.R. § 1.97(g) and (h), the filing of this IDS should not be construed as a representation that a search had been made or that information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56 (b), or that any cited document listed or attached is (or constitutes) prior art. Unless otherwise indicated, the date of

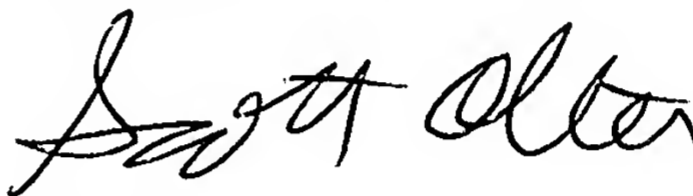
Serial No. 10/665,165

publication indicated for an item is taken from the face of the item, and Applicant reserves the right to prove that the date of publication is in fact different.

No fee is believed to be required; however, the Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

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(PTO-1449)

SERIAL NO.
10/665,165

APPLICANT
Joseph Young J. PAIK


FILING DATE
September 18, 2003

GROUP

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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EXAMINER			DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <div style="text-align: center;">  <p>(PTO-1449)</p> </div>		ATTY. DOCKET NO. 007734 USA/ FPS/MMCS/APC	SERIAL NO. 10/665,165
		APPLICANT Joseph Young J. PAIK	
		FILING DATE September 18, 2003	GROUP
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	Guo, R.S., A. Chen, C.L. Tseng, I.K. Fong, A. Yang, C.L. Lee, C.H. Wu, S. Lin, S.J. Huang, Y.C. Lee, S.G. Chang, and M.Y. Lee. June 16-17, 1998. "A Real-Time Equipment Monitoring and Fault Detection System." <i>Semiconductor Manufacturing Technology Workshop</i> , pp. 111-121.		
	Lantz, Mikkel. 1999. "Equipment and APC Integration at AMD with Workstream." <i>IEEE</i> , pp. 325-327.		
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	August 18, 2004. International Preliminary Examination Report for PCT Serial No. PCT/US02/19116.		
	August 24, 2004. Office Action for U.S. Serial No. 10/135,405, filed May 1, 2002.		
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EXAMINER		DATE CONSIDERED	

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